

RESEARCH PAPER

SiGe heterojunction bipolar phototransistor for optics–microwaves interfacing

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A new SiGe heterojunction bipolar phototransistor (HPT) based on a commercially available process was designed, realized, and experimentally characterized. Its internal characteristics, mainly the collector-to-base capacitance, vary significantly with the received light power, making it suitable as an active element of a light-controlled photo-oscillator. It can also be a key component of optical network-on-chip (ONoC). Its responsivity was improved and its transition frequency remains in the range of 30 GHz.

Keywords: Photodetection, Phototransistor, Radio over fiber, Optical Networks on Chip, SiGe.

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I. INTRODUCTION

Interest of silicon–germanium (SiGe) heterostructures on silicon for optical receivers in short-wavelength (850 nm) transmission systems and networks is well recognized [1]. Its main advantages are improved speed and responsivity combined with cost effectiveness and the ability to be integrated in high-speed silicon analog or digital circuits. Several structures were proposed [2, 3].

We have designed and characterized a new structure of SiGe heterojunction bipolar phototransistor (HPT), showing a significant dependence of its internal characteristics (mainly the collector-to-base capacitance and the time constants of the current source), with the received light power, which was not reported until now. It can be used in the new receiver structure for optics–microwave interfacing in radio-over-fiber networks we have previously proposed [4]. It is based on a photo-oscillator designed to operate at a central frequency that can be chosen in the range of 5–12 GHz. A frequency deviation of several tens of MHz may be controlled by illumination. In this paper, we investigate thoroughly the HPT by itself, mainly its equivalent circuit variations under illumination, to derive what might be the maximum frequency deviation of a photo-oscillator in which the HPT would be the key component, but could have many other applications [5].

The phototransistor was designed by modifying a heterojunction bipolar transistor (HBT) in 0.35 μm commercially available technology from AMS (Austria Mikro Systems). Removing a base finger creates an illumination window. This structure was

improved since the first one [6], in order to enhance the efficiency without degrading the transition frequency: the main modification consists of an increase in the transistor length to get a larger illuminated area. Nevertheless, we chose not to increase the dimension of the illumination window in the other direction to preserve the transition frequency of the device and to remain compatible with commercial RF Foundry services, in contrast with other designs aiming to optimize the responsivity [7]. Its geometry makes it also suitable as an integrated receiver in optical network-on-chip (ONoC) on silicon using optical planar waveguides.

New measurements reported here concern the HPT equivalent elements depending on the photocurrent induced by the received light and on the bias point. These measurements have confirmed the possibility to use it as active element of a photo-oscillator whose oscillation frequency decreases linearly with the received power, converting an OOK optical signal into a frequency or phase-modulated radio frequency (RF) carrier. This detection scheme could be an interesting and cost-effective alternative to RF transmission over fiber [8].

II. THE HPT

Its base has a gradual Ge concentration up to $\text{Si}_{0.8}\text{Ge}_{0.2}$, and a thickness of about 10 nm. Its sensitivity is high up to a wavelength of 0.95 μm [9], which is suitable for low cost, high bit-rate large area networks (LANs) using Vertical Cavity Surface-Emitting Laser (VCSEL) transmitters at 0.85 μm . To transform the HBT into an HPT with improved detection efficiency, the metallization of one base finger was suppressed and the length of the illuminated zone was increased up to 12 μm (Fig. 1).

We have experimentally verified that the intrinsic characteristics of the transistor were not modified. Alone among extrinsic elements, the base access resistance R_{b1} increases significantly (from 25 to 60 Ω), due to the suppression of a metalization finger.

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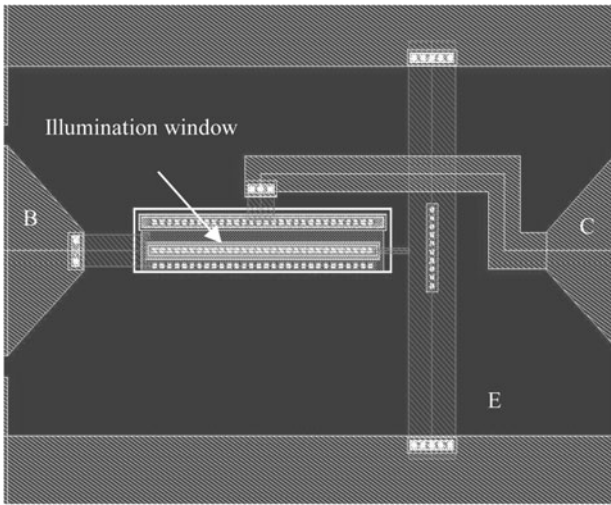


Fig. 1. Layout of the phototransistor.

III. STATIC MEASUREMENTS

The phototransistor was characterized on a test bench and was illuminated through a tapered multimode fiber powered by a 0.85 μm VCSEL at its other end. Static measurement of the photocurrent I_{PH} was performed in photodiode mode ($V_{be} = 0$) depending on the optical power P at the fiber end (Fig. 2). The characteristic is rather linear with a slight saturation effect at high illumination. The measured responsivity is $R = 0.066$ A/W, thus an external efficiency of 15% with respect to its theoretical value [6], this low value is simply due to the non-optimization of the fiber-to-detector coupling. In a previous experiment, we had achieved a higher efficiency ($R = 0.15$ A/W) with a sharper fiber end. Due to the internal structure of the phototransistor (directly derived from a foundry transistor) and its optimization in transition frequency, no gain was observed in the phototransistor mode compared to the photodiode mode, as in [5, 10, 11]. But our purpose was to use the phototransistor as a tunable oscillator, not as amplifier.

Another set of measurements concerned the emitter-to-base static characteristics (Fig. 3). It shows in the dark the classical nkT log shape of a diode with $n \approx 2.8$ (instead of 2 in [2]), but when illuminated with 950 μW, a current rather proportional to V_{be} is superposed to the diode current, at least below base-emitter diode threshold voltage, which can be modeled by a photo conductance in parallel with the diode.

IV. EQUIVALENT PARAMETERS MEASUREMENTS

A) Modelling

We used the classical model shown in Fig. 4 and the methods developed for its parameters extraction [12–15]. Measurements of the Z-matrix (extracted from the S-matrix over the 1.5–20 GHz range, after an Line, Reflect, Match (LRM) calibration of the HP8510C VNA) allow the determination of following elements:

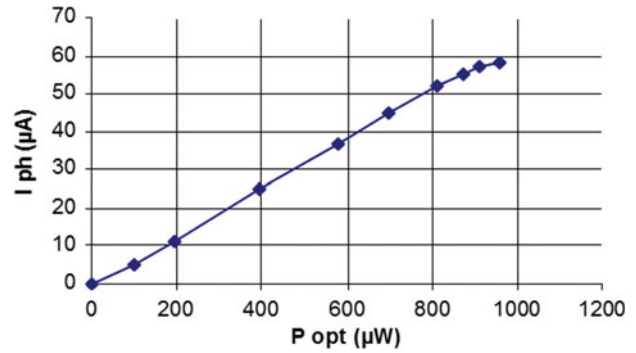


Fig. 2. Photocurrent I_{PH} versus received power P .

R_{b1} is the physical access resistance, it is near 60 Ω and rather less dependent on bias and received optical power P ; R_{b2} and R_e correspond to the base-to-emitter junction, they follow the classical nkT/qI_b law; moreover, the emitter resistance R_e decreases when P increases, which is due to photoconductivity; C_e has a negligible admittance (Z_e is quasi-real) and cannot be significantly extracted from measurement with accurate values;

R_c is quasi-infinite (Z_c is quasi-imaginary and represented by C_c) and cannot be extracted from measurement with accurate values either; it should be kept in mind that element values extracted from S-parameters cannot be determined accurately when their impedance is either very high or very low with respect to the reference impedance, which is the present case; and the current gain α and time constants τ_1

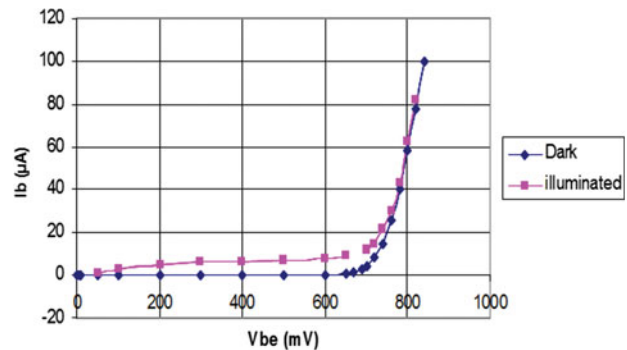


Fig. 3. Base to emitter junction characteristics.

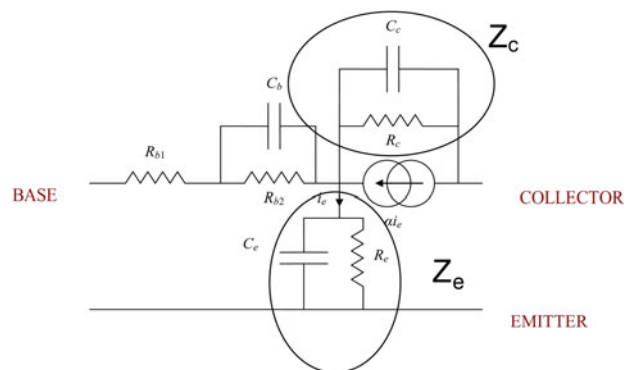


Fig. 4. Equivalent model of the phototransistor.

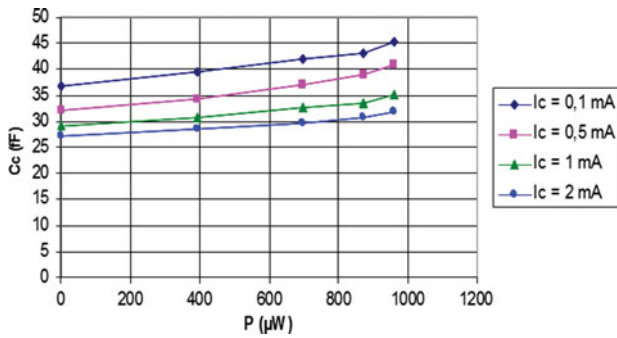


Fig. 5. Variation of capacitance C_c with the received power P .

(delay) and τ_2 (relaxation time) come from:

$$\alpha = \alpha_0 \frac{e^{-j\omega\tau_1}}{1 + j\omega\tau_2} = \frac{Z_{12} - Z_{21}}{Z_{22} - X_{21}}$$

with $\alpha_0 \approx 0.995$ corresponding to static $\beta \approx 200$.

B) Results

Measurements of these parameters were performed in the range 1.5–20 GHz at different biasing points versus optical power P . The most significant results concern the capacitance C_c (Fig. 5) and delay time τ_1 (Fig. 6), which both increase significantly and rather linearly with the received power P . We have also extracted the parallel capacitance $C_{b'e}$ of a classical Giacoletto scheme [16], which was also found to be increasing rather linearly with P (Fig. 7), enabling the decreasing of the photo-oscillator frequency under illumination.

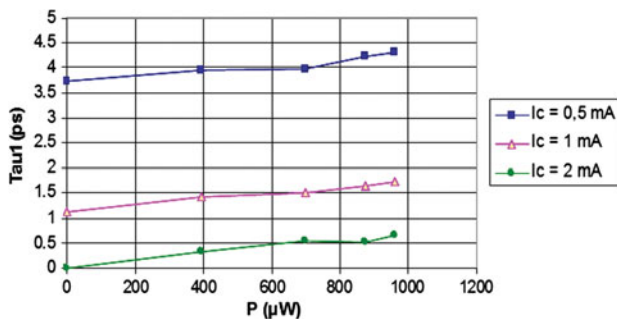


Fig. 6. Variation of time constant τ_1 with the received power P .

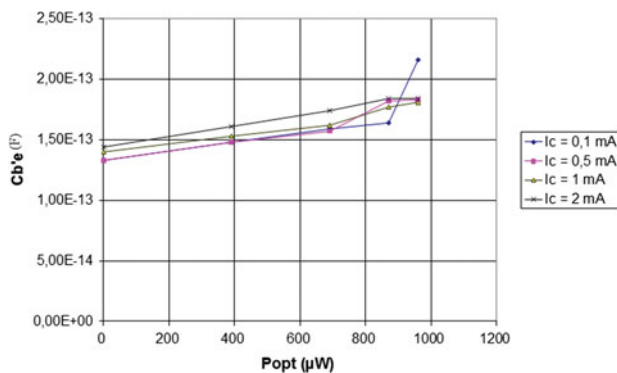


Fig. 7. Variation of parallel capacitance $C_{b'e}$ with received power P .

The physical reason for all these effects could be the decrease in the depletion width under optical injection. τ_1 decreases when I_c increases (τ_2 , which is an Resistance-Capacitor (RC) time constant, remains nearly constant). It allows the design of a photo-oscillator whose frequency decreases when the optical power increases, which was demonstrated by simulation [4]. C_c decreases when the bias voltage V_{ce} increases.

C) Transition frequency

Derived from the S-matrix, transition frequency was found to be in the range of 20–50 GHz depending on the biasing point, increasing strongly with I_c (it reaches 50 GHz at $I_c = 2$ mA). It decreases slightly when P increases, which is correlated to the capacitance increase.

V. CONCLUSION

The experiments performed on the prototypes of this new phototransistor confirm its ability to be the active element of a light-controlled photo-oscillator for optical–microwave interfacing in hybrid access networks, as well as other devices such as integrated photo-receivers for ONoC.

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